1. Open the chiller water line.
2. Open the system from the MAIN POWER switch.

3. For venting the chamber push the “VENT” switch to up position and wait until the chamber door opens easily. When the lid is opened close the “VENT” switch by pushing it down.

4. Put your sample inside the chamber upside. (process surface at up position) Close the chamber lid and turn the “VACUUM” switch on.
5. Before starting the process, you have to wait for the pressure going below 50 mTorr.

6. When the pressure is reached, turn on the “GAS 2” line for Oxygen. In this system for now we only have oxygen.

7. Gas flow is generally set to 100 mTorr pressure, but if you want to change the chamber pressure, you can do it by rotating the “GAS 2” knob at the right side of the system.

8. When desired pressure is reached, turn on the RF power source from MAIN POWER button.

9. When the RF source is turned on, set the desired RF power with the ARROW BUTTONS.

10. Because there is NOT a timer on this system, you should bring a timer with you before starting the process.

11. When the pressure, RF power and required time is set, you can start the process by pressing “RF ON/OFF” button.
12. After pressing the “RF ON/OFF” button, you should set the “Reflected RF Power” as close to “zero” as possible by rotating the “TUNE” and the “LOAD” RF matching capacitor knobs.

13. When required time is finished for your process, turn off the RF power from “RF ON/OFF” button.

14. Stop the gas flow by turning off the “GAS 2” line switch.

15. Turn off the “VACUUM” switch.

16. Vent the chamber from the “VENT” switch.

17. When chamber is vent, open the lid, take your sample out.

18. Close the lid and pump down the chamber for “2” minutes by using the “VACUUM” switch.

19. Shut down the system from the MAIN POWER switch.

20. Turn off the chiller water lines.